

**METHOD OF LITHOGRAPHIC IMAGE ALIGNMENT FOR USE WITH A DUAL  
MASK EXPOSURE TECHNIQUE**

**ABSTRACT OF THE DISCLOSURE**

5       Methods of fabricating an integrated circuit on a wafer using dual mask exposure lithography is disclosed. Improved mask image alignment between a first mask image and a second mask image of a dual mask exposure technique can be achieved by aligning the second mask image to a latent image created by an exposure using the first mask image.

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